

MANUFACTURING METHOD OF GLASS SUBSTRATE FOR MAGNETIC DISC AND
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Abstract of the Disclosure

In a cleansing step to cleanse a glass substrate carried out between a rough polishing step and a mirror polishing step, the glass substrate is caused to be in contact with a cleansing liquid including ascorbic acid, fluorine ion of between 100 ppm and 1000 ppm, and sulfuric acid of 3% by weight or more. Thus, even if surface roughness is increased by etching accompanying cleansing, the surface roughness occurs within a range of cutting stock to be polished in the mirror polishing to be carried out later.

Fig. 2